Christopher K Ober

List of Publications by Year
in descending order

547 papers	29,731 citations	6254 80 h-index	6653 156 g-index
593 all docs	593 docs citations	593 times ranked	25029 citing authors

#	Article	IF	Citations
1	Emerging applications of stimuli-responsive polymer materials. Nature Materials, 2010, 9, 101-113.	27.5	5,007
2	Nanocomposite Materials for Optical Applications. Chemistry of Materials, 1997, 9, 1302-1317.	6.7	998
3	Advances in polymers for anti-biofouling surfaces. Journal of Materials Chemistry, 2008, 18, 3405.	6.7	741
4	An Efficient Two-Photon-Generated Photoacid Applied to Positive-Tone 3D Microfabrication. Science, 2002, 296, 1106-1109.	12.6	709
5	Competing Interactions and Levels of Ordering in Self-Organizing Polymeric Materials. Science, 1997, 277, 1225-1232.	12.6	701
6	Self-Assembled Monolayers and Polymer Brushes in Biotechnology:Â Current Applications and Future Perspectives. Biomacromolecules, 2005, 6, 2427-2448.	5.4	661
7	Attogram detection using nanoelectromechanical oscillators. Journal of Applied Physics, 2004, 95, 3694-3703.	2.5	547
8	Self-Assembled Smectic Phases in Rod-Coil Block Copolymers. Science, 1996, 273, 343-346.	12.6	417
9	50th Anniversary Perspective: Polymer Brushes: Novel Surfaces for Future Materials. Macromolecules, 2017, 50, 4089-4113.	4.8	393
10	Anti-Biofouling Properties of Comblike Block Copolymers with Amphiphilic Side Chains. Langmuir, 2006, 22, 5075-5086.	3.5	331
11	Particle size control in dispersion polymerization of polystyrene. Canadian Journal of Chemistry, 1985, 63, 209-216.	1.1	329
12	Liquid Crystalline, Semifluorinated Side Group Block Copolymers with Stable Low Energy Surfaces:Â Synthesis, Liquid Crystalline Structure, and Critical Surface Tension. Macromolecules, 1997, 30, 1906-1914.	4.8	311
13	Comparison of the Fouling Release Properties of Hydrophobic Fluorinated and Hydrophilic PEGylated Block Copolymer Surfaces:Â Attachment Strength of the DiatomNaviculaand the Green AlgaUlva. Biomacromolecules, 2006, 7, 1449-1462.	5.4	261
14	Polyelectrolyte-Surfactant Complexes in the Solid State: Facile building blocks for self-organizing materials. Advanced Materials, 1997, 9, 17-31.	21.0	254
15	Surface Segregation Studies of Fluorine-Containing Diblock Copolymersâ€. Macromolecules, 1996, 29, 1229-1234.	4.8	231
16	Molecular Design, Synthesis, and Characterization of Liquid Crystalâ^'Coil Diblock Copolymers with Azobenzene Side Groups. Macromolecules, 1997, 30, 2556-2567.	4.8	225
17	Thermotropic Liquid Crystalline Polyesters with Rigid or Flexible Spacer Groups. British Polymer Journal, 1980, 12, 132-146.	0.7	224
18	Recent progress in high resolution lithography. Polymers for Advanced Technologies, 2006, 17, 94-103.	3.2	222

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19	Block copolymer patterns and templates. Materials Today, 2006, 9, 30-39.	14.2	222
20	Zigzag Morphology of a Poly(styrene-b-hexyl isocyanate) Rod-Coil Block Copolymer. Macromolecules, 1995, 28, 1688-1697.	4.8	208
21	Monodispersed, micron-sized polystyrene particles by dispersion polymerization. Journal of Polymer Science, Polymer Letters Edition, 1985, 23, 103-108.	0.4	202
22	Formation of large monodisperse copolymer particles by dispersion polymerization. Macromolecules, 1987, 20, 268-273.	4.8	188
23	Study of the interlayer expansion mechanism and thermalâ€“mechanical properties of surface-initiated epoxy nanocomposites. Polymer, 2002, 43, 4895-4904.	3.8	188
24	Extreme ultraviolet resist materials for sub-7 nm patterning. Chemical Society Reviews, 2017, 46, 4855-4866.	38.1	185
25	Reworkable Epoxies:Â Thermosets with Thermally Cleavable Groups for Controlled Network Breakdown. Chemistry of Materials, 1998, 10, 1475-1482.	6.7	183
26	An overview of supercritical CO2 applications in microelectronics processing. Microelectronic Engineering, 2003, 65, 145-152.	2.4	180
27	Deformation of a Polydomain, Liquid Crystalline Epoxy-Based Thermoset. Macromolecules, 1998, 31, 4074-4088.	4.8	167
28	Orthogonal Patterning of PEDOT:PSS for Organic Electronics using Hydrofluoroether Solvents. Advanced Materials, 2009, 21, 2314-2317.	21.0	165
29	Control of biofouling on reverse osmosis polyamide membranes modified with biocidal nanoparticles and antifouling polymer brushes. Journal of Materials Chemistry B, 2014, 2, 1724.	5.8	164
30	Dissociation Behavior of Weak Polyelectrolyte Brushes on a Planar Surface. Langmuir, 2009, 25, 4774-4779.	3.5	161
31	Liquid crystalline and rigid-rod networks. Progress in Polymer Science, 1993, 18, 899-945.	24.7	154
32	Reinforcement of Polymer Interfaces with Random Copolymers. Physical Review Letters, 1994, 73, 2472-2475.	7.8	154
33	Reversible Morphology Control in Block Copolymer Films via Solvent Vapor Processing: An in Situ GISAXS Study. Macromolecules, 2010, 43, 4253-4260.	4.8	154
34	Control of Self-Assembly of Lithographically Patternable Block Copolymer Films. ACS Nano, 2008, 2, 1396-1402.	14.6	149
35	Research in Macromolecular Science: Challenges and Opportunities for the Next Decade. Macromolecules, 2009, 42, 465-471.	4.8	145
36	Hydrofluoroethers as Orthogonal Solvents for the Chemical Processing of Organic Electronic Materials. Advanced Materials, 2008, 20, 3481-3484.	21.0	142

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37	ABC Triblock Surface Active Block Copolymer with Grafted Ethoxylated Fluoroalkyl Amphiphilic Side Chains for Marine Antifouling/Fouling-Release Applications. Langmuir, 2009, 25, 12266-12274.	3.5	141
38	Patterned Biofunctional Poly(acrylic acid) Brushes on Silicon Surfaces. Biomacromolecules, 2007, 8, 3082-3092.	5.4	140
39	Liquid Crystal Polymers. V. Thermotropic Polyesters with Either Dyad or Triad Aromatic Ester Mesogenic Units and Flexible Polymethylene Spacers in the Main Chain. Polymer Journal, 1982, 14, 9-17.	2.7	138
40	Oligo(ethylene glycol) Containing Polymer Brushes as Bioselective Surfaces. Langmuir, 2005, 21, 2495-2504.	3.5	132
41	Characterization of thermally reworkable thermosets: materials for environmentally friendly processing and reuse. Polymer, 2002, 43, 131-139.	3.8	131
42	Alignment of Self-Assembled Hierarchical Microstructure in Liquid Crystalline Diblock Copolymers Using High Magnetic Fields. Macromolecules, 2004, 37, 9903-9908.	4.8	128
43	Coatings Based on Side-chain Ether-linked Poly(ethylene glycol) and Fluorocarbon Polymers for the Control of Marine Biofouling. Biofouling, 2003, 19, 91-98.	2.2	126
44	The effect of temperature and initiator levels on the dispersion polymerization of polystyrene. Journal of Polymer Science Part A, 1987, 25, 1395-1407.	2.3	125
45	Patternable Block Copolymers. , 0, , 183-226.		122
46	Surfaces of Fluorinated Pyridinium Block Copolymers with Enhanced Antibacterial Activity. Langmuir, 2006, 22, 11255-11266.	3.5	121
47	Settlement of Ulva Zoospores on Patterned Fluorinated and PEGylated Monolayer Surfaces. Langmuir, 2008, 24, 503-510.	3.5	121
48	Polymer-Based Marine Antifouling and Fouling Release Surfaces: Strategies for Synthesis and Modification. Annual Review of Chemical and Biomolecular Engineering, 2019, 10, 241-264.	6.8	118
49	The Orientation of Semifluorinated Alkanes Attached to Polymers at the Surface of Polymer Films. Macromolecules, 2000, 33, 1882-1887.	4.8	115
50	Release of Nerve Growth Factor from HEMA Hydrogel-Coated Substrates and Its Effect on the Differentiation of Neural Cells. Biomacromolecules, 2009, 10, 174-183.	5.4	114
51	Liquid crystalline epoxy thermosets based on dihydroxymethylstilbene: Synthesis and characterization. Journal of Polymer Science Part A, 1992, 30, 1831-1843.	2.3	111
52	Semifluorinated Aromatic Side-Group Polystyrene-Based Block Copolymers:Â Bulk Structure and Surface Orientation Studies. Macromolecules, 2002, 35, 8078-8087.	4.8	111
53	Rigid rod and liquid crystalline thermosets. Progress in Polymer Science, 1997, 22, 975-1000.	24.7	110
54	Surface Stability in Liquid-Crystalline Block Copolymers with Semifluorinated Monodendron Side Groups. Macromolecules, 2000, 33, 6106-6119.	4.8	110

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55	Orthogonal processing: A new strategy for organic electronics. Chemical Science, 2011, 2, 1178.	7.4	109
56	Design and application of high-sensitivity two-photon initiators for three-dimensional microfabrication. Journal of Photochemistry and Photobiology A: Chemistry, 2003, 158, 163-170.	3.9	108
57	Controlled degradation of epoxy networks: analysis of crosslink density and glass transition temperature changes in thermally reworkable thermosets. Polymer, 2004, 45, 1939-1950.	3.8	106
58	A General Approach to Controlling the Surface Composition of Poly(ethylene oxide)-Based Block Copolymers for Antifouling Coatings. Langmuir, 2011, 27, 13762-13772.	3.5	106
59	Self-Organizing Materials with Low Surface Energy:Â The Synthesis and Solid-State Properties of Semifluorinated Side-Chain Ionenes. Macromolecules, 1997, 30, 7560-7567.	4.8	105
60	Molecular Glass Resists for High-Resolution Patterning. Chemistry of Materials, 2006, 18, 3404-3411.	6.7	104
61	Direct Three-Dimensional Microfabrication of Hydrogels via Two-Photon Lithography in Aqueous Solution. Chemistry of Materials, 2009, 21, 2003-2006.	6.7	104
62	Deformation of a Polydomain, Smectic Liquid Crystalline Elastomer. Macromolecules, 1998, 31, 8531-8539.	4.8	103
63	Fluorinated Amphiphilic Polymers and Their Blends for Fouling-Release Applications: The Benefits of a Triblock Copolymer Surface. ACS Applied Materials & Interfaces, 2011, 3, 3366-3374.	8.0	103
64	Two-Photon Three-Dimensional Microfabrication of Poly(Dimethylsiloxane) Elastomers. Chemistry of Materials, 2004, 16, 5556-5558.	6.7	102
65	Synthesis and Characterization of Thermally Degradable Polymer Networks. Chemistry of Materials, 1998, 10, 3833-3838.	6.7	101
66	Spatially Controlled Fabrication of Nanoporous Block Copolymers. Chemistry of Materials, 2004, 16, 3800-3808.	6.7	100
67	Orientation of Liquid Crystalline Epoxides under ac Electric Fields. Macromolecules, 1997, 30, 4278-4287.	4.8	99
68	The mechanical and magnetic alignment of liquid crystalline epoxy thermosets. Journal of Polymer Science Part A, 1992, 30, 1845-1853.	2.3	98
69	Additive-Driven Phase-Selective Chemistry in Block Copolymer Thin Films: The Convergence of Topâ€“Down and Bottomâ€“Up Approaches. Advanced Materials, 2004, 16, 953-957.	21.0	97
70	Amphiphilic Surface Active Triblock Copolymers with Mixed Hydrophobic and Hydrophilic Side Chains for Tuned Marine Fouling-Release Properties. Langmuir, 2010, 26, 9772-9781.	3.5	97
71	Block copolymers containing liquid crystalline segments. Acta Polymerica, 1997, 48, 405-422.	0.9	95
72	Triblock Copolymers with Grafted Fluorine-Free, Amphiphilic, Non-Ionic Side Chains for Antifouling and Fouling-Release Applications. Macromolecules, 2011, 44, 4783-4792.	4.8	94

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73	Low-Surface-Energy Fluoromethacrylate Block Copolymers with Patternable Elements. Chemistry of Materials, 2000, 12, 33-40.	6.7	92
74	Supercritical CO2Processing for Submicron Imaging of Fluoropolymers. Chemistry of Materials, 2000, 12, 41-48.	6.7	89
75	Stress relaxation of a main-chain, smectic, polydomain liquid crystalline elastomer. Polymer, 1998, 39, 3713-3718.	3.8	88
76	Fluorine-free mixed amphiphilic polymers based on PDMS and PEG side chains for fouling release applications. Biofouling, 2011, 27, 589-602.	2.2	86
77	Widely Tunable Morphologies in Block Copolymer Thin Films Through Solvent Vapor Annealing Using Mixtures of Selective Solvents. Advanced Functional Materials, 2015, 25, 3057-3065.	14.9	86
78	Molecular glass photoresists for advanced lithography. Journal of Materials Chemistry, 2006, 16, 1693.	6.7	84
79	Temperature Dependence of Molecular Orientation on the Surfaces of Semifluorinated Polymer Thin Films. Langmuir, 2000, 16, 1993-1997.	3.5	83
80	Control of Surface Properties Using Fluorinated Polymer Brushes Produced by Surface-Initiated Controlled Radical Polymerization. Langmuir, 2004, 20, 10498-10506.	3.5	83
81	Sub-50 nm feature sizes using positive tone molecular glass resists for EUV lithography. Journal of Materials Chemistry, 2006, 16, 1470.	6.7	83
82	Rigid-rod thermosets based on 1,3,5-triazine-linked aromatic ester segments. Macromolecules, 1992, 25, 2947-2954.	4.8	82
83	Molecular Glass Resists as Highâ€Resolution Patterning Materials. Advanced Materials, 2008, 20, 3355-3361.	21.0	82
84	Role of Solvent Dielectric Properties on Charge Transfer from PbS Nanocrystals to Molecules. Nano Letters, 2010, 10, 318-323.	9.1	79
85	High-Performance Electron-Transporting Polymers Derived from a Heteroaryl Bis(trifluoroborate). Journal of the American Chemical Society, 2011, 133, 9949-9951.	13.7	78
86	Zinc induced polyelectrolyte coacervate bioadhesive and its transition to a self-healing hydrogel. RSC Advances, 2015, 5, 66871-66878.	3.6	78
87	Protein adsorption resistance of anti-biofouling block copolymers containing amphiphilic side chains. Soft Matter, 2010, 6, 3237.	2.7	77
88	Chemically Amplified Positive Resists for Two-Photon Three-Dimensional Microfabrication. Advanced Materials, 2003, 15, 517-521.	21.0	76
89	Synthesis and curing of novel LC twin epoxy monomers for liquid crystal thermosets. Journal of Polymer Science Part A, 1996, 34, 1291-1303.	2.3	75
90	Engineering low surface energy polymers through molecular design: synthetic routes to fluorinated polystyrene-based block copolymers. Journal of Materials Chemistry, 2002, 12, 1684-1692.	6.7	74

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91	Liquid Crystalline Rodâ^'Coil Block Copolymers by Stable Free Radical Polymerization:Â Synthesis, Morphology, and Rheology. Macromolecules, 2003, 36, 3357-3364.	4.8	74
92	Amplification by optical composites. Optics Letters, 1997, 22, 1247.	3.3	73
93	Studying the Mechanism of Hybrid Nanoparticle Photoresists: Effect of Particle Size on Photopatterning. Chemistry of Materials, 2015, 27, 5027-5031.	6.7	73
94	Synthesis and characterization of pyrene-labeled hydroxypropyl cellulose and its fluorescence in solution. Macromolecules, 1987, 20, 38-44.	4.8	72
95	Detection of Transmitter Release from Single Living Cells Using Conducting Polymer Microelectrodes. Advanced Materials, 2011, 23, H184-8.	21.0	71
96	Orientation-On-Demand Thin Films: Curing of Liquid Crystalline Networks in ac Electric Fields. Science, 1996, 272, 252-255.	12.6	70
97	Understanding and controlling the morphology of styreneâ€“isoprene side-group liquid crystalline diblock copolymers. Polymer, 2000, 41, 8897-8907.	3.8	70
98	Methods for the Topographical Patterning and Patterned Surface Modification of Hydrogels Based on Hydroxyethyl Methacrylate. Biomacromolecules, 2003, 4, 1126-1131.	5.4	70
99	Direct Patterning of Intrinsically Electron Beam Sensitive Polymer Brushes. ACS Nano, 2010, 4, 771-780.	14.6	69
100	Amphiphilic triblock copolymers with PEGylated hydrocarbon structures as environmentally friendly marine antifouling and fouling-release coatings. Biofouling, 2014, 30, 589-604.	2.2	69
101	Polymer brushes for electrochemical biosensors. Soft Matter, 2011, 7, 297-302.	2.7	68
102	Electrical Control of Protein Conformation. Advanced Materials, 2012, 24, 2501-2505.	21.0	67
103	Acid-Sensitive Semiperfluoroalkyl Resorcinarene: An Imaging Material for Organic Electronics. Journal of the American Chemical Society, 2008, 130, 11564-11565.	13.7	66
104	Role of Backbone Chemistry and Monomer Sequence in Amphiphilic Oligopeptide- and Oligopeptoid-Functionalized PDMS- and PEO-Based Block Copolymers for Marine Antifouling and Fouling Release Coatings. Macromolecules, 2017, 50, 2656-2667.	4.8	66
105	Metalâ€“Organic Framework-Inspired Metal-Containing Clusters for High-Resolution Patterning. Chemistry of Materials, 2018, 30, 4124-4133.	6.7	65
106	Linear viscoelasticity of side chain liquid crystal polymer. Liquid Crystals, 1993, 13, 233-245.	2.2	62
107	Fluorinated mesogen-jacketed liquid-crystalline polymers as surface-modifying agents: Design, synthesis and characterization. Macromolecular Chemistry and Physics, 2002, 203, 1573-1583.	2.2	62
108	Selective Area Control of Self-Assembled Pattern Architecture Using a Lithographically Patternable Block Copolymer. ACS Nano, 2009, 3, 1761-1766.	14.6	61

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109	Fouling-resistant polymer brush coatings. Polymer, 2011, 52, 5419-5425.	3.8	61
110	Orientational Switching of Mesogens and Microdomains in Hydrogen-Bonded Side-Chain Liquid-Crystalline Block Copolymers Using AC Electric Fields. Advanced Functional Materials, 2004, 14, 364-370.	14.9	60
111	A glucose sensor via stable immobilization of the GOx enzyme on an organic transistor using a polymer brush. Journal of Polymer Science Part A, 2015, 53, 372-377.	2.3	58
112	Transverse Cylindrical Microdomain Orientation in an LC Diblock Copolymer under Oscillatory Shear. Macromolecules, 1999, 32, 7703-7706.	4.8	57
113	Perpendicular Orientation Control without Interfacial Treatment of RAFT-Synthesized High-Ï‡ Block Copolymer Thin Films with Sub-10 nm Features Prepared via Thermal Annealing. ACS Applied Materials & Interfaces, 2017, 9, 31266-31278.	8.0	57
114	Block copolymers with low surface energy segments: siloxane- and perfluoroalkane-modified blocks. Polymer, 1995, 36, 1321-1325.	3.8	56
115	High refractive index and high transparency HfO2 nanocomposites for next generation lithography. Journal of Materials Chemistry, 2010, 20, 5186.	6.7	56
116	Molecular Orientation of Single and Two-Armed Monodendron Semifluorinated Chains on â€œSoftâ€•and â€œHardâ€•Surfaces Studied Using NEXAFS. Macromolecules, 2000, 33, 6068-6077.	4.8	55
117	Surface Organization, Light-Driven Surface Changes, and Stability of Semifluorinated Azobenzene Polymers. Langmuir, 2007, 23, 5110-5119.	3.5	55
118	Responsive and patterned polymer brushes. Journal of Polymer Science, Part B: Polymer Physics, 2013, 51, 1457-1472.	2.1	55
119	Smectic rheology. Rheologica Acta, 1997, 36, 498-504.	2.4	54
120	Nanoparticle photoresists from HfO2 and ZrO2 for EUV patterning. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2012, 25, 583-586.	0.3	54
121	Liquid-crystalline polymers. 12. Polyesters with either alternating or random orientation of mesogenic units. Macromolecules, 1983, 16, 1034-1036.	4.8	53
122	Effect of Changing Molecular End Groups on Surface Properties:Â Synthesis and Characterization of Poly(styrene-b-semifluorinated isoprene) Block Copolymers with â^'CF2H End Groups. Macromolecules, 2000, 33, 8012-8019.	4.8	53
123	Microphase-Stabilized Ferroelectric Liquid Crystals (MSFLC):Â Bistable Switching of Ferroelectric Liquid Crystalâ^'Coil Diblock Copolymers. Chemistry of Materials, 1998, 10, 1538-1545.	6.7	52
124	Three-Dimensional Microfabrication by Two-Photon Lithography. MRS Bulletin, 2005, 30, 976-982.	3.5	52
125	Control and Suppression of Surface Relief Gratings in Liquid-Crystalline Perfluoroalkylâ€“Azobenzene Polymers. Advanced Functional Materials, 2006, 16, 1577-1581.	14.9	52
126	A novel noria (water-wheel-like cyclic oligomer) derivative as a chemically amplified electron-beam resist material. Journal of Materials Chemistry, 2008, 18, 3588.	6.7	52

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127	Surface engineering of styrene/PEGylatedâ€fluoroalkyl styrene block copolymer thin films. Journal of Polymer Science Part A, 2009, 47, 267-284.	2.3	52
128	Ambiguous antiâ€fouling surfaces: Facile synthesis by lightâ€mediated radical polymerization. Journal of Polymer Science Part A, 2016, 54, 253-262.	2.3	51
129	Solubility studies of inorganicâ€“organic hybrid nanoparticle photoresists with different surface functional groups. Nanoscale, 2016, 8, 1338-1343.	5.6	51
130	Analysis of smectic structure formation in liquid crystalline thermosets. Polymer, 1997, 38, 5857-5867.	3.8	50
131	Mesogen-jacketed liquid crystalline polymers via stable free radical polymerization. Macromolecular Chemistry and Physics, 1999, 200, 2338-2344.	2.2	50
132	Fluorinated polymers: liquid crystalline properties and applications in lithography. Chemical Record, 2004, 4, 315-330.	5.8	49
133	Functionalized Surface Arrays for Spatial Targeting of Immune Cell Signaling. Journal of the American Chemical Society, 2006, 128, 5594-5595.	13.7	49
134	An Efficient Route to Mesoporous Silica Films with Perpendicular Nanochannels. Advanced Materials, 2008, 20, 246-251.	21.0	49
135	Patterning of Polymer Brushes. A Direct Approach to Complex, Sub-Surface Structures. Nano Letters, 2010, 10, 3873-3879.	9.1	49
136	Antimicrobial Behavior of Semifluorinated-Quaternized Triblock Copolymers against Airborne and Marine Microorganisms. ACS Applied Materials & Interfaces, 2010, 2, 703-711.	8.0	49
137	Viscoelastic properties of a model mainâ€chain liquid crystalline polyether. Journal of Rheology, 1994, 38, 1623-1638.	2.6	48
138	Study of the Structureâ^'Properties Relationship of Phenolic Molecular Glass Resists for Next Generation Photolithography. Chemistry of Materials, 2008, 20, 1606-1613.	6.7	48
139	Cellular Responses to Patterned Poly(acrylic acid) Brushes. Langmuir, 2011, 27, 7016-7023.	3.5	48
140	A brief guide to polymer nomenclature (IUPAC Technical Report). Pure and Applied Chemistry, 2012, 84, 2167-2169.	1.9	48
141	Impact of the synthesis method on the solid-state charge transport of radical polymers. Journal of Materials Chemistry C, 2018, 6, 111-118.	5.5	48
142	Title is missing!. Die Makromolekulare Chemie Rapid Communications, 1983, 4, 49-55.	1.1	47
143	Selectively Thermally Cleavable Fluorinated Side Chain Block Copolymers:Â Surface Chemistry and Surface Properties. Macromolecules, 2000, 33, 1310-1320.	4.8	47
144	High-Resolution Patterning of Molecular Glasses Using Supercritical Carbon Dioxide. Advanced Materials, 2006, 18, 442-446.	21.0	47

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145	Rod-coil block copolymers: An iterative synthetic approach via living free-radical procedures. Journal of Polymer Science Part A, 2003, 41, 3640-3656.	2.3	46
146	Characterization of the Photoacid Diffusion Length and Reaction Kinetics in EUV Photoresists with IR Spectroscopy. Macromolecules, 2010, 43, 4275-4286.	4.8	46
147	Metal Oxide Nanoparticle Photoresists for EUV Patterning. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2014, 27, 663-666.	0.3	46
148	NEXAFS Depth Profiling of Surface Segregation in Block Copolymer Thin Films. Macromolecules, 2010, 43, 4733-4743.	4.8	45
149	Biomimetic Polymer Brushes Containing Tethered Acetylcholine Analogs for Protein and Hippocampal Neuronal Cell Patterning. Biomacromolecules, 2013, 14, 529-537.	5.4	45
150	Flexible Hydrophobic Antifouling Coating with Oriented Nanotopography and Nonleaking Capsaicin. ACS Applied Materials & Interfaces, 2018, 10, 9718-9726.	8.0	45
151	Surface Induced Tilt Propagation in Thin Films of Semifluorinated Liquid Crystalline Side Chain Block Copolymers. Macromolecules, 2007, 40, 81-89.	4.8	43
152	Effects of surface-active block copolymers with oxyethylene and fluoroalkyl side chains on the antifouling performance of silicone-based films. Biofouling, 2016, 32, 81-93.	2.2	43
153	Diazonaphthoquinone Molecular Glass Photoresists:Â Patterning without Chemical Amplification. Chemistry of Materials, 2007, 19, 3780-3786.	6.7	42
154	Dry photolithographic patterning process for organic electronic devices using supercritical carbon dioxide as a solvent. Journal of Materials Chemistry, 2008, 18, 3087.	6.7	42
155	Engineered nanomaterials and human health: Part 1. Preparation, functionalization and characterization (IUPAC Technical Report). Pure and Applied Chemistry, 2018, 90, 1283-1324.	1.9	41
156	The Role of Hydrogen Bonding in Peptoid-Based Marine Antifouling Coatings. Macromolecules, 2019, 52, 1287-1295.	4.8	41
157	Non-ionic photo-acid generators for applications in two-photon lithography. Journal of Materials Chemistry, 2009, 19, 505-513.	6.7	40
158	Dual Mode Patterning of Fluorine-Containing Block Copolymers through Combined Top-down and Bottom-up Lithography. Chemistry of Materials, 2012, 24, 1454-1461.	6.7	40
159	Nanoparticle Photoresists: Ligand Exchange as a New, Sensitive EUV Patterning Mechanism. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2013, 26, 659-664.	0.3	40
160	Solid state crystalline and liquid crystalline structure of semifluorinated 1-bromoalkane compounds. Liquid Crystals, 1999, 26, 637-648.	2.2	39
161	POLYMER SCIENCE:Shape Persistence of Synthetic Polymers. Science, 2000, 288, 448-449.	12.6	39
162	Preventing Nonspecific Adsorption on Polymer Brush Covered Gold Electrodes Using a Modified ATRP Initiator. Biomacromolecules, 2009, 10, 2750-2758.	5.4	39

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163	Semiperfluoroalkyl Polyfluorenes for Orthogonal Processing in Fluorous Solvents. Macromolecules, 2010, 43, 1195-1198.	4.8	39
164	Reconstruction of Surfaces from Mixed Hydrocarbon and PEG Components in Water: Responsive Surfaces Aid Fouling Release. Biomacromolecules, 2012, 13, 1864-1874.	5.4	39
165	Dispersion copolymerization in nonâ€aqueous media. Makromolekulare Chemie Macromolecular Symposia, 1990, 35-36, 87-104.	0.6	38
166	Heat capacity measurements of two-dimensional self-assembled hexadecanethiol monolayers on polycrystalline gold. Applied Physics Letters, 2004, 84, 5198-5200.	3.3	38
167	Orthogonal Processing and Patterning Enabled by Highly Fluorinated Lightâ€Emitting Polymers. Advanced Materials, 2011, 23, 735-739.	21.0	38
168	Highly Reactive 2,5-Disubstituted Styrene-Based Monomer Polymerized via Stable Free Radical Polymerization:Â Effect of Substitution and Liquid Crystallinity on Polymerization. Macromolecules, 2001, 34, 5120-5124.	4.8	37
169	Enzymatic Surface-Initiated Polymerization:Â A Novel Approach for the in Situ Solid-Phase Synthesis of Biocompatible Polymer Poly(3-hydroxybutyrate). Biomacromolecules, 2004, 5, 889-894.	5.4	37
170	Patterning of Polymeric Hydrogels for Biomedical Applications. Macromolecular Rapid Communications, 2001, 22, 1284.	3.9	36
171	A new inorganic EUV resist with high-etch resistance. Proceedings of SPIE, 2012, , .	0.8	36
172	Molecular Dynamics of a Liquid Crystalline Polymer Studied by Two-Dimensional Fourier Transform and CW ESR. The Journal of Physical Chemistry, 1996, 100, 15873-15885.	2.9	35
173	Influence of a liquid crystalline block on the microdomain structure of block copolymers. Macromolecular Symposia, 1997, 117, 241-256.	0.7	35
174	Imaging polymers with supercritical carbon dioxide. Advanced Materials, 1997, 9, 1039-1043.	21.0	35
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